

IN THE U.S. PATENT AND TRADEMARK OFFICE

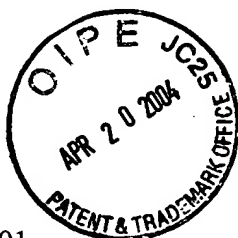
In re patent application of

Ferrera et al.

Serial No.: 09/809,766

Filed: March 15, 2001

For: SPATIAL PHASE LOCKING WITH SHAPED ELECTRON BEAM
LITHOGRAPHY



Group Art Unit: 2881

Examiner: P. Gurzo

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Sir:

A Notice of Allowance and Fee(s) Due has issued on February 24, 2004 for the above-identified patent application. The issue fee has not been paid. This Information Disclosure Statement is being timely submitted, concurrently with a Request for Continued Examination (RCE), in response to the Notice of Allowance and Fee(s) Due.

Under the provisions of 37 C.F.R. 1.97 through 1.98 and pursuant to applicant's duty of disclosure under 37 C.F.R. 1.56, applicant respectfully brings the following documents, listed on the attached form PTO-1449, to the attention of the Examiner in charge of the above-identified application. Copies of the listed documents are provided herewith for the convenience of the Examiner.

This citation does not constitute an admission that the references are relevant or material to the claims. They are only cited as constituting related art of which the applicant is aware.

It is respectfully requested that the listed references be considered by the Examiner and formally made of record in this application.

If it is deemed appropriate at this point in prosecution, please charge any necessary fees in connection with this Information Disclosure Statement to deposit account number 09-0458 (International Business Machines Corporation - Fishkill).

Respectfully submitted,

Marshall M. Curtis

Reg. No.: 33,138

Whitham, Curtis & Christofferson, P.C.
11491 Sunset Hills Road, Suite 340
Reston, VA 20190
(703) 787-9400
Customer Number 30743

INFORMATION DISCLOSURE CITATION

(Use several sheets if necessary)

Docket Number (Optional)

FIS920000237 (00750430AA)

Application Number

09/809,766

Applicant(s)

Ferrera et al.

Filing Date

03/15/2001

Group Art Unit

2881

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	REF	DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE IF APPROPRIATE

FOREIGN PATENT DOCUMENTS

	REF	DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	Translation	
							YES	NO

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)

		Goodberlet et al.; "A One-Dimensional Demonstration of Spatial-Phase-Locked Electron-Beam Lithography"; Elsevier Science B.V. - Microelectronic Engineering; 1997; pgs. 473-476
		Goodberlet et al.; "Extending Spatial-Phase-Locked Electron Beam Lithography to Two Dimensions"; Jpn. J. Appl. Phys., Vol. 36, Pt. 1, No. 12B; 1997; pgs. 7557-7559

EXAMINER

DATE CONSIDERED

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP Section 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.